

Abstract

Device for Handling a Semiconductor Wafer in an Epitaxy Reactor and Method for Producing a Semiconductor Wafer Having an Epitaxial Layer

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Device for handling a semiconductor wafer in an epitaxy reactor and method for producing a semiconductor wafer having an epitaxial layer. The device comprises a susceptor; longitudinal holes extending through the susceptor; a wafer lifting shaft; wafer lifting pins, which are guided through the longitudinal holes; a susceptor

10 carrying shaft; susceptor carrying arms; susceptor support pins; guide sleeves, which are anchored in the susceptor carrying arms; and guide elements, which protrude from the guide sleeves and, at upper ends, have bores into which the wafer lifting pins are inserted, and which can be raised and lowered together with the wafer lifting pins by means of the wafer lifting shaft.

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Drawing for the abstract: Fig.1